L Number	Hits	Search Text	DB	Time stamp
- Number	1815	(phase adj shift\$3 same (mask or photomask	USPAT;	2003/04/30 14:30
	1010	or reticle)) same (resist or photoresist	US-PGPUB;	
		or photosensit\$4)	EPO; JPO;	
		or photosome	IBM TDB	
	798	((phase adj shift\$3 same (mask or	USPAT;	2003/04/28 16:37
_	, , , ,	photomask or reticle)) same (resist or	US-PGPUB;	
		photoresist or photosensit\$4)) and (trim	EPO; JPO;	·
		or ((mask or photomask or reticle) near3	IBM TDB	
		set) or (second or complementary) adj	_	
		(mask or photomask or reticle) or		
1		overla\$5)		
	126	(((phase adj shift\$3 same (mask or	USPAT;	2003/04/28 16:25
_	120	photomask or reticle)) same (resist or	US-PGPUB;	
		photoresist or photosensit\$4)) and (trim	EPO; JPO;	1
		or ((mask or photomask or reticle) near3	IBM TDB	
		set) or (second or complementary) adj	1511_100	
		(mask or photomask or reticle) or		
		overla\$5)) and (transistor near3 gate or		
	0.7	gate adj shr?nk\$3)	USPAT;	2003/04/28 16:25
_	97	((((phase adj shift\$3 same (mask or	US-PGPUB;	2000,01,20 10.20
		photomask or reticle)) same (resist or	EPO; JPO;	
		photoresist or photosensit\$4)) and (trim	IBM TDB	
		or ((mask or photomask or reticle) near3	101-100	
1		set) or (second or complementary) adj		
		(mask or photomask or reticle) or		
}		overla\$5)) and (transistor near3 gate or		
		gate adj shr?nk\$3)) and (resolution or		
		resolv\$3)	HCDAM.	2003/04/28 16:26
-	. 89		USPAT;	2003/04/20 10:20
		photomask or reticle)) same (resist or	US-PGPUB;	ā
		photoresist or photosensit\$4)) and (trim	EPO; JPO;	
		or ((mask or photomask or reticle) near3	IBM_TDB	
		set) or (second or complementary) adj		
		(mask or photomask or reticle) or		
		overla\$5)) and (transistor near3 gate or		
		gate adj shr?nk\$3)) and (resolution or		
		resolv\$3)) and (optical adj (parameter or		
		configurat\$3) or aperture or (wavelength		
		or coherenc\$1 or illumina\$4 or focus or		
		defocus) same (expos\$3 or radia\$4 or	•	
		irradia\$4 or light or illumina\$4))	TIGE DAM	2004/02/12 11 14
-	65		USPAT;	2004/02/13 11:14
		photomask or reticle)) same (resist or	US-PGPUB;	
		photoresist or photosensit\$4)) and (trim	EPO; JPO;	
		or ((mask or photomask or reticle) near3	IBM_TDB	1
		set) or (second or complementary) adj		
		(mask or photomask or reticle) or		
		overla\$5)) and (transistor near3 gate or		i i
		gate adj shr?nk\$3)) and (resolution or		
		resolv\$3)) and (optical adj (parameter or		
		configurat\$3) or aperture or (wavelength		
		or coherenc\$1 or illumina\$4 or focus or		
		defocus) same (expos\$3 or radia\$4 or		
		irradia\$4 or light or illumina\$4))) and		
		(dose or dosage or intensity)		
		(dose of dosage of intensity)	L	

			.,	
-	24	((((((phase adj shift\$3 same (mask or	USPAT;	2004/02/13 11:15
		photomask or reticle)) same (resist or	US-PGPUB;	
		photoresist or photosensit\$4)) and (trim	EPO; JPO;	
		or ((mask or photomask or reticle) near3	IBM_TDB	
		set) or (second or complementary) adj		
		(mask or photomask or reticle) or	Ì	
		overla\$5)) and (transistor near3 gate or	Ì	
		gate adj shr?nk\$3)) and (resolution or		
		resolv\$3)) and (optical adj (parameter or		
		configurat\$3) or aperture or (wavelength		
		or coherenc\$1 or illumina\$4 or focus or		
		defocus) same (expos\$3 or radia\$4 or		
		irradia\$4 or light or illumina\$4))) not		
÷		((((((phase adj shift\$3 same (mask or		
		photomask or reticle)) same (resist or		·
		photoresist or photosensit\$4)) and (trim		
		or ((mask or photomask or reticle) near3		
		set) or (second or complementary) adj		
		(mask or photomask or reticle) or		
		overla\$5)) and (transistor near3 gate or		
		gate adj shr?nk\$3)) and (resolution or		
				·
		resolv\$3)) and (optical adj (parameter or		
		configurat\$3) or aperture or (wavelength		
		or coherenc\$1 or illumina\$4 or focus or		
		defocus) same (expos\$3 or radia\$4 or		
		irradia\$4 or light or illumina\$4))) and		
	}	(dose or dosage or intensity))		
_	2	(("20020187636") or ("20020197543")).PN.	USPAT;	2003/04/28 16:33
			US-PGPUB;	
			EPO; JPO;	
			IBM TDB	
i	22	(("6284419") or ("6519501") or	USPAT;	2003/04/28 16:34
_				2003/04/20 10.34
		("20020076622") or ("6453457") or	US-PGPUB;	
		("6337172") or ("6541165") or ("6503666")	EPO; JPO;	
		or ("6162568") or ("6255024") or	IBM_TDB	*
1		("6268091") or ("6319644") or ("6421111")		
1		or ("5972569") or ("5405721") or		
		("6042973") or ("6127096") or ("6374396")		
		or ("6096457") or ("6106979") or		
		("6040892") or ("6120952") or		
		("5741624")).PN.		
	21		USPAT;	2003/04/28 16:35
	21	("20020197543")).PN.) or ((("6284419") or	US-PGPUB	2000, 01, 20 10:00
		("6519501") or ("20020076622") or	35 13101	
		("EAE2457") or ("E227172") ("EE4116"")		
	1 .	("6453457") or ("6337172") or ("6541165")		
		or ("6503666") or ("6162568") or	1	
		("6255024") or ("6268091") or ("6319644")		
		or ("6421111") or ("5972569") or		
		("5405721") or ("6042973") or ("6127096")		
		or ("6374396") or ("6096457") or		
		("6106979") or ("6040892") or ("6120952")		
	1	or ("5741624")).PN.)) not (((((phase adj	+	
		shift\$3 same (mask or photomask or		
		reticle)) same (resist or photoresist or		1
		photosensit\$4)) and (trim or ((mask or		
		, , , , , , , , , , , , , , , , , , ,		
	1	photomask or reticle) near3 set) or		
		(second or complementary) adj (mask or		
		photomask or reticle) or overla\$5)) and		
		(transistor near3 gate or gate adj		
		shr?nk\$3)) and (resolution or resolv\$3))		
		and (optical adj (parameter or		
		configurat\$3) or aperture or (wavelength		
l .		or coherenc\$1 or illumina\$4 or focus or		
		defocus) same (expos\$3 or radia\$4 or irradia\$4 or light or illumina\$4)))		

_	398	((430/5,311-312,319,394,396 or 355/53,77	USPAT;	2004/02/13 11:17
		or 378/34-35 or 716/19-21).ccls. and	US-PGPUB;	
		(phase adj shift\$3 same (mask or photomask	EPO; JPO;	
	1	or reticle)) same (trim or ((mask or	IBM TDB	1
		photomask or reticle) near3 set) or	_	
		(second or complementary) adj (mask or		
		photomask or reticle) or overla\$5)) not		
		(((((phase adj shift\$3 same (mask or		
		photomask or reticle)) same (resist or		1
		photoresist or photosensit\$4)) and (trim		
		or ((mask or photomask or reticle) near3		
	}	set) or (second or complementary) adj		
		set) of (second of complementary) adj		
		(mask or photomask or reticle) or	·	
1		overla\$5)) and (transistor near3 gate or	0 /	
		gate adj shr?nk\$3)) and (resolution or		1
		resolv\$3)) and (optical adj (parameter or		
		configurat\$3) or aperture or (wavelength		
		or coherenc\$1 or illumina\$4 or focus or		
		defocus) same (expos\$3 or radia\$4 or		
		irradia\$4 or light or illumina\$4)))		0000101100
-	4	(("5885734") or ("6077630") or	USPAT;	2003/04/28 18:09
		("20010000240") or ("20010028985")).PN.	US-PGPUB	
_	48	(("4037918") or ("4456371") or ("5302477")	USPAT;	2003/04/30 14:58
120		or ("5308741") or ("5316878") or	US-PGPUB	
		("5324600") or ("5328807") or ("5334542")		
		or ("5352550") or ("5364716") or		
		("5424154") or ("5480746") or ("5496666")		
		or ("5498579") or ("5503951") or		
		("5523186") or ("5527645") or ("5532090")		
		or ("5537648") or ("5538815") or		
	1	("5539568") or ("5565286") or ("5573890")		
		or ("5595843") or ("5620816") or		
		("5635316") or ("5636131") or ("5702848")		
÷		or ("5725969") or ("5761075") or		
		("5766804") or ("5766806") or ("5807649")		
		or ("5827623") or ("5858580") or		
		("5885734") or ("5923566") or ("5994002")	/ / /	
		or ("5998068") or ("6004702") or		
		("6010807") or ("6057063") or ("6066180")		
		or ("6077630") or ("6083275") or		
		("6228539") or ("6251549") or	-	
		("6258493")).PN.		
_	9	(("5472814") or ("5923562") or ("6130012")	USPAT;	2003/04/30 15:02
		or ("6139994") or ("6185727") or	US-PGPUB	
		("6335128") or ("6338922") or		
		("20010000240") or ("20010028985")).PN.		
	12	(("6420074") or ("6436590") or	USPAT;	2003/04/30 15:06
		("20020083410") or ("20020122994") or	US-PGPUB	
	İ	("20020127479") or ("20020129327") or		
		("20020136964") or ("20020142231") or		
	1	("20020142232") or ("20020144232") or		
		("20020152454") or ("20020155363")).PN.		
_	6		USPAT;	2004/02/13 11:17
		adj shift\$3 adj (mask or reticle or	US-PGPUB;	
		photomask) same (resist or photoresist))	EPO; JPO;	
*		and 430/5.ccls.	IBM TDB	
_		("6524752").PN.	USPAT;	2003/05/08 16:46
	1	, ,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,	US-PGPUB	
	4	((full adj phase adj shift\$3 or full adj	USPAT;	2004/02/13 11:18
_	4	phase) adj (mask or reticle or photomask))	US-PGPUB;	
		not (((full or complete or overall) adj	EPO; JPO;	
		phase adj shift\$3 adj (mask or reticle or	IBM TDB	
		photomask) same (resist or photoresist))		
		and 430/5.ccls.)		
1		1 0 0 0 0 0 0 0 0 0 0 0 0 0 0 0	<u> </u>	

_	357	((dose or dosing or dosage or intensity)	USPAT;	2003/05/13 18:49
		same (second adj (mask or photomask or	US-PGPUB;	
		reticle))) not	EPO; JPO;	
		(((430/5,311-312,319,394,396 or 355/53,77	IBM TDB	
		(((430/5,311-312,319,394,390 01 333/33,77	1511_155	
		or 378/34-35 or 716/19-21).ccls. and		
		(phase adj shift\$3 same (mask or photomask		
		or reticle)) same (trim or ((mask or		
		photomask or reticle) near3 set) or		
		(second or complementary) adj (mask or		
		(second of complementary) adj (mask of		
		photomask or reticle) or overla\$5)) not		
		((((((phase adj shift\$3 same (mask or		l i
-		photomask or reticle)) same (resist or		
		photoresist or photosensit\$4)) and (trim		
		or ((mask or photomask or reticle) near3		
		or ((mask of photomask of feeter) hears		ļ
	ļ	set) or (second or complementary) adj		
İ		(mask or photomask or reticle) or		
		overla\$5)) and (transistor near3 gate or		
		gate adj shr?nk\$3)) and (resolution or		
		resolv\$3)) and (optical adj (parameter or		t
		resolvas)) and (optical ad) (parameter of		
1 .		configurat\$3) or aperture or (wavelength	7	
		or coherenc\$1 or illumina\$4 or focus or		°
		defocus) same (expos\$3 or radia\$4 or		4
		irradia\$4 or light or illumina\$4))))		
1			USPAT;	2004/02/13 11:19
_	16	(((dose or dosing or dosage or intensity)		2004/02/13 11:19
		same (second adj (mask or photomask or	US-PGPUB;	
		reticle))) not	EPO; JPO;	
1	1	(((430/5,311-312,319,394,396 or 355/53,77	IBM TDB	
		or 378/34-35 or 716/19-21).ccls. and	_	
		UL J/0/J4-JJ OL /IU/IJ Z1/.CCIJ. and		
1		(phase adj shift\$3 same (mask or photomask		
		or reticle)) same (trim or ((mask or		
		photomask or reticle) near3 set) or		
		(second or complementary) adj (mask or		
		photomask or reticle) or overla\$5)) not		
1		photomask of recipies of overraps, mode		
		((((((phase adj shift\$3 same (mask or		
	-	photomask or reticle)) same (resist or		
		photoresist or photosensit\$4)) and (trim		
		or ((mask or photomask or reticle) near3	1	
		set) or (second or complementary) adj		
		set) or (second of complementary) adj		
1		(mask or photomask or reticle) or		
		overla\$5)) and (transistor near3 gate or		
		gate adj shr?nk\$3)) and (resolution or		
		resolv\$3)) and (optical adj (parameter or	1	
		TESOTIVOS/ ATTA (OPETCAT da) (parameter of		
		configurat\$3) or aperture or (wavelength		
		or coherenc\$1 or illumina\$4 or focus or	1	
		defocus) same (expos\$3 or radia\$4 or		
		irradia\$4 or light or illumina\$4))))) and		
	,	(resist or photoresist) and phase adj		
		shift\$3 same (mask or photomask or		
		reticle)		
_	92		USPAT;	2004/02/13 11:15
		photomask or reticle)) same (resist or	US-PGPUB;	
		photomask of recticle, same (resist of photoresist or photosensit\$4)) and (trim	EPO; JPO;	
		photoresist of photosensit()4// and (trim		
		or ((mask or photomask or reticle) near3	IBM_TDB	
		set) or (second or complementary) adj		
		(mask or photomask or reticle) or		
		overla\$5)) and (transistor near3 gate or		
		gate adj shr?nk\$3)) and (resolution or		
		gate adj shrinkasi, and (resolution of		
		resolv\$3)) and (optical adj (parameter or		
		configurat\$3) or aperture or (wavelength		
		or coherenc\$1 or illumina\$4 or focus or		
1		defocus) same (expos\$3 or radia\$4 or		
		irradia\$4 or light or illumina\$4))) and		
		Tiradiasa or fight of firmuridaally and		
1	1	(dose or dosage or intensity)	1	1

				200 4 /00 /20 22 23
	37	((((((phase adj shift\$3 same (mask or	USPAT;	2004/02/13 11:16
	•	photomask or reticle)) same (resist or	US-PGPUB;	~
		photoresist or photosensit\$4)) and (trim	EPO; JPO;	
		or ((mask or photomask or reticle) near3	IBM TDB	
		set) or (second or complementary) adj	-	
		set) or (second of complementary) and		
		(mask or photomask or reticle) or		
		overla\$5)) and (transistor near3 gate or		
		gate adj shr?nk\$3)) and (resolution or		·
ĺ		resolv\$3)) and (optical adj (parameter or		
		configurat\$3) or aperture or (wavelength		
		or coherenc\$1 or illumina\$4 or focus or		
		defocus) same (expos\$3 or radia\$4 or		
		irradia\$4 or light or illumina\$4))) not		
		(((((((phase adj shift\$3 same (mask or	. *	
		((((((phase ad) shirts) same (mask or		
		photomask or reticle)) same (resist or		
		photoresist or photosensit\$4)) and (trim		
		or ((mask or photomask or reticle) near3		
		set) or (second or complementary) adj		
		(mask or photomask or reticle) or		
		overla\$5)) and (transistor near3 gate or		
	:	gate adj shr?nk\$3)) and (resolution or		
		resolv\$3)) and (optical adj (parameter or	] .	
		resolvas)) and (optical adj (parameter or		
		configurat\$3) or aperture or (wavelength		
		or coherenc\$1 or illumina\$4 or focus or		
		defocus) same (expos\$3 or radia\$4 or		
		irradia\$4 or light or illumina\$4))) and		
		(dose or dosage or intensity))		
	495	((430/5,311-312,319,394,396 or 355/53,77	USPAT;	2004/02/13 11:17
	150	or 378/34-35 or 716/19-21).ccls. and	US-PGPUB;	
		(phase adj shift\$3 same (mask or photomask	EPO; JPO;	
		or reticle)) same (trim or ((mask or	IBM TDB	
		or reticle)) same (trim or (mask or	12.1_132	
		photomask or reticle) near3 set) or		
		(second or complementary) adj (mask or		
		photomask or reticle) or overla\$5)) not		
	, ,	((((((phase adj shift\$3 same (mask or		
		photomask or reticle)) same (resist or		
		photoresist or photosensit\$4)) and (trim		
		or ((mask or photomask or reticle) near3		
		set) or (second or complementary) adj		
		(mask or photomask or reticle) or		
		(Mask of photomask of fectors) of		
		overla\$5)) and (transistor near3 gate or		
		gate adj shr?nk\$3)) and (resolution or		
		resolv\$3)) and (optical adj (parameter or		
		configurat\$3) or aperture or (wavelength		
		or coherenc\$1 or illumina\$4 or focus or		
		defocus) same (expos\$3 or radia\$4 or		
1	1 -	irradia\$4 or light or illumina\$4)))		
		((full or complete or overall) adj phase	USPAT;	2004/02/13 11:17
-	/	adj shift\$3 adj (mask or reticle or	US-PGPUB;	
		adj shiitaa adj (mask of feetere of	EPO; JPO;	
		<pre>photomask) same (resist or photoresist))</pre>	IBM TDB	
	1	and 430/5.ccls.	_	2004/02/13 11:18
_	8	((full adj phase adj shift\$3 or full adj	USPAT;	2004/02/13 11:18
		phase) adj (mask or reticle or photomask))	US-PGPUB;	
		not (((full or complete or overall) adj	EPO; JPO;	
		phase adj shift\$3 adj (mask or reticle or	IBM_TDB	
		photomask) same (resist or photoresist))	_	
		and 430/5.ccls.)		
1	1	and 400/0.0013./		

	20	(((dose or dosing or dosage or intensity)	USPAT;	2004/02/13	11:19
-	20	same (second adj (mask or photomask or	US-PGPUB;		
			EPO; JPO;		
		reticle))) not	IBM TDB		
		(((430/5,311-312,319,394,396 or 355/53,77	1511_1515		
		or 378/34-35 or 716/19-21).ccls. and			
		(phase adj shift\$3 same (mask or photomask			
		or reticle)) same (trim or ((mask or			
1		photomask or reticle) near3 set) or			
		(second or complementary) adj (mask or			
		photomask or reticle) or overla\$5)) not			
		((((((phase adj shift\$3 same (mask or	e		
		photomask or reticle)) same (resist or			
		photoresist or photosensit\$4)) and (trim			
		or ((mask or photomask or reticle) near3			
		set) or (second or complementary) adj			
		(mask or photomask or reticle) or			
		overla\$5)) and (transistor near3 gate or			
		gate adj shr?nk\$3)) and (resolution or			
		resolv\$3)) and (optical adj (parameter or			
		configurat\$3) or aperture or (wavelength			
		or coherenc\$1 or illumina\$4 or focus or			
		defocus) same (expos\$3 or radia\$4 or			
		irradia\$4 or light or illumina\$4))))) and			
		(resist or photoresist) and phase adj			
		shift\$3 same (mask or photomask or			
		reticle)			